MALLA REDDY ENGINEERING COLLEGE (AUTONOMOUS) (Affiliated to JAWAHARLAL NEHRU TECHNOLOGICAL UNIVERSITY HYDERABAD)

Gundlapochampally (H), Maisammaguda (V), Medchal (M), Medchal-Malkajgiri (Dist), Hyderabad

IV B.TECH I SEMESTER SUPPLEMENTARY EXAMINATIONS, DECEMBER-2018

Subject: Digital Image Processing

Branch: ECE

Time: 3 hours	Max. Marks: 75
Answer any FIVE Questions of the following	5x15M=75M
1. a) Write a short notes on	(8M)
i) Neighbors of pixels ii) Sampling and quantization of an i	mage.
b) Differentiate between Walsh and Hadamard transform.	(7M)
2. a) Explain various image enhancement techniques by point processing.	(8M)
b) With the help of necessary expressions explain how differentiation is hel	pful in
image sharpening.	(7M)
3. a) Explain smoothing techniques in frequency domain for image enhancem	nent. (8M)
b) Explain the following techniques.	(7M)
i) Unsharp masking ii) High boost filtering	
4. a) Write a short notes on Inverse filtering and Least mean square filtering.	. (7M)
b) What is Wiener filter? Explain.	(8M)
5. a) What is an image edge? Explain about Prewitt and Sobel operators in e	dge
detection.	(8M)
b) Explain about Global processing via Graph-Theoretical techniques.	(7M)
6. a) Draw the block diagram of image compression model and explain each	block. (7M)
b) Explain about JPEG 2000 standards.	(8M)
7. a) Explain the role of wavelet transforms in image processing with examp	oles. (7M)
b) Write a short notes on discrete wavelet transforms.	(8M)
8. a) Explain about opening and closing operations.	(8M)
b) What are logical operations involved in binary images.	(7M)

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IV B.TECH I SEMESTER SUPPLEMENTARY EXAMINATIONS, NOVEMBER-2018

Subject: <u>VLSI DESIGN</u>

Branch: ECE		
Time: 3 hours Max. Marks	s: 75	
Answer any FIVE Questions of the following 5x15M=75M	5x15M=75M	
 a) Explain the various steps involved in the N-well CMOS fabrication process with the neat diagrams. 	help of [10]	
b) Why ion-implantation is preferred over diffusion for impurity doping? Explain briefly implantation technique.	ion- [5]	
2. a) Explain about the BiCMOS inverters with neat diagrams.b) Derive the drain current and drain voltage relationship for an N-channel Enhancemen MOSFET for different regions of operation.	[7] t [8]	
 3. a) Design a stick diagram of 'OR' gate? b) Design a layout for equation Y=A\(\bar{B}\) + \(\bar{A}\)B 		
 4. a) Explain domino logic in detail. b) Compute the ON resistance (VDD to GND) of an NMOS inverter having pull-up to play down ratio of 4:1, if n-channel sheet resistance, Rsn = 10⁴ Ω per square. 	[8M] oull- [7M]	
5. a) Design and explain a Manchester carry chain?b) Explain the SRAM with a differential pair sense amplifier?		
6. a) Implement the following Boolean functions using PLA.	[8]	
FI(A,B,C) = $\sum (1,2,4,6)$ F2(A,B,C)= $\sum (0,1,6,7)$ F3(A,B,C)= $\sum (2,4,5,6,7)$ b) Draw and explain architecture of CPLD with neat sketches.	[7]	
7. a) Explain the Implementation of VHDL programming on devices using flow?		
b) Explain the RTL synthesis varied with the targeted to the Device synthesis		
8 a) What is the need of Test and Testability in VLSI system design. Explain.	[8]	
b) Explain the Boundary scan system level test technique.	[7]	